<u></u>	·	· · · · · · · · · · · · · · · · · · ·		<del>,,</del>
L Number	Hits	Search Text	DB	Time stamp
1	2034	(359/290,291,294,298,223).CCLS.	USPAT;	2004/10/22
-	2001	(303,230,231,231,230,220,10020	US-PGPUB;	15:27
			EPO; JPO;	
			DERWENT	
2	8345	micromirror\$1 or micro-mirror\$1 or (micro	USPAT;	2004/10/22
		adj2 mirror\$1)	US-PGPUB;	15:28
		-	EPO; JPO;	
			DERWENT	
3	1843007	substrate\$1	USPAT;	2004/10/22
			US-PGPUB;	15:28
			EPO; JPO;	
	4005	1161	DERWENT	2004/10/22
4	4925	((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom)	USPAT; US-PGPUB;	2004/10/22 15:29
		adj2 layer\$1) and ((second\$3 of bottom)   adj2 silicon adj2 layer\$1)	EPO; JPO;	15.29
		adje silicon adje layerili	DERWENT	
5	40008	(mirror\$1 or reflect\$3) adj2 (plate\$1 or	USPAT;	2004/10/22
Ĭ	10000	template\$1 or board\$1)	US-PGPUB;	15:29
	,	complator of souldry	EPO; JPO;	1
	1		DERWENT	
6	4809	hydrogen adj2 treatment	USPAT;	2004/10/22
		,	US-PGPUB;	15:29
			EPO; JPO;	
			DERWENT	
7	15874	gas near4 sputter\$3	USPAT;	2004/10/22
			US-PGPUB;	15:30
			EPO; JPO;	
	2000		DERWENT	2004/10/22
8	3888	(micromirror\$1 or micro-mirror\$1 or	USPAT;	2004/10/22
		(micro adj2 mirror\$1)) and substrate\$1	US-PGPUB;	15:30
			EPO; JPO; DERWENT	
9	36	(((first or primary or top) adj2 silicon	USPAT;	2004/10/22
		adj2 layer\$1) and ((second\$3 or bottom)	US-PGPUB;	15:30
-	1	adj2 silicon adj2 layer\$1)) and	EPO; JPO;	2000
		((micromirror\$1 or micro-mirror\$1 or	DERWENT	
		(micro adj2 mirror\$1)) and substrate\$1)		
10	7	((mirror\$1 or reflect\$3) adj2 (plate\$1 or	USPAT;	2004/10/22
		template\$1 or board\$1)) and (((first or	US-PGPUB;	15:30
		primary or top) adj2 silicon adj2	EPO; JPO;	
		layer\$1) and ((second\$3 or bottom) adj2	DERWENT	
		silicon adj2 layer\$1)) and		
		((micromirror\$1 or micro-mirror\$1 or		
11	_	(micro adj2 mirror\$1)) and substrate\$1))	IISDAT.	2004/10/22
11		(hydrogen adj2 treatment) and ((mirror\$1 or reflect\$3) adj2 (plate\$1 or template\$1	USPAT; US-PGPUB;	15:30
		or board\$1)) and (((first or primary or	EPO; JPO;	10.00
		top) adj2 silicon adj2 layer\$1) and	DERWENT	
		((second\$3 or bottom) adj2 silicon adj2		
		layer\$1)) and ((micromirror\$1 or		
	1	micro-mirror\$1 or (micro adj2 mirror\$1))		
		and substrate\$1)))		
12	100		USPAT;	2004/10/22
		sputter\$3)	US-PGPUB;	15:30
		· .	EPO; JPO;	
		l	DERWENT	0004/10/00
13	0	(micromirror\$1 or micro-mirror\$1 or	USPAT;	2004/10/22
		(micro adj2 mirror\$1)) and ((hydrogen	US-PGPUB;	15:30
		adj2 treatment) and (gas near4	EPO; JPO;	
14		sputter\$3))   ((359/290,291,294,298,223).CCLS.) and	DERWENT USPAT;	2004/10/22
+4	4	((359/290,291,294,298,223).CCLS.) and (((mirror\$1 or reflect\$3) adj2 (plate\$1	USPAT; US-PGPUB;	15:31
		or template\$1 or board\$1)) and (((first	EPO; JPO;	10.01
		or primary or top) adj2 silicon adj2	DERWENT	
		layer\$1) and ((second\$3 or bottom) adj2		
		silicon adj2 layer\$1)) and		
		((micromirror\$1 or micro-mirror\$1 or		
		<pre>(micro adj2 mirror\$1)) and substrate\$1)))</pre>		

15	0 (	((359/290,291,294,298,223).CCLS.) and	USPAT;	2004/10/22
	(	((hydrogen adj2 treatment) and (gas near4	US-PGPUB;	15:31
	s	sputter\$3))	EPO; JPO;	
			DERWENT	